IN THE CLAIMS

Please amend the claims as follows:

Claims 1-25 (Canceled).

Claim 26 (Previously Presented): A vapor deposition material comprising a polycrystalline body, a sintered body, or single crystal having a surface covered with a fluoride layer, wherein the fluoride layer comprises a material of formula

 MO_XF_Y ,

wherein M is Mg, Ca, Sr, Ba, an alkali earth compound metal, a rare earth metal, or a compound metal of an alkali earth metal and rare earth metal, and 0 < X < 2 and $0 < Y \le 4$.

Claims 27-28 (Canceled).

Claim 29 (Previously Presented): An FPD obtained by vapor depositing the vapor deposition material according to claim 26 onto a substrate.

Claim 30 (Previously Presented): The vapor deposition material according to Claim 26, wherein the fluoride layer is from 0.1 nm to 100 µm in thickness.

Claim 31 (Previously Presented): The vapor deposition material according to Claim 26, wherein the fluoride layer is from 1 nm to 1 µm in thickness.

Claim 32 (Previously Presented): The vapor deposition material of Claim 26, wherein the entire surface of the polycrystalline body, sintered body, or single crystal is covered with a fluoride layer.

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Claim 33 (Previously Presented): The vapor deposition material of Claim 26, comprising a polycrystalline body covered with a fluoride layer.

Claim 34 (Previously Presented): The vapor deposition material of Claim 26, comprising a sintered body covered with a fluoride layer.

Claim 35 (Previously Presented): The vapor deposition material of Claim 26, comprising a single crystal covered with a fluoride layer.

Claim 36 (Previously Presented): The vapor deposition material of Claim 26, wherein $0.25 \le X < 2$.

Claim 37 (Previously Presented): The vapor deposition material of Claim 26, wherein $0.5 \le X < 2$.

Claim 38 (Previously Presented): The vapor deposition material of Claim 26, wherein $1 \le Y \le 4$.

Claim 39 (Previously Presented): The vapor deposition material of Claim 26, wherein the fluoride layer is a material selected from the group consisting of MO_{0.5}F, MO_{0.25}F_{1.25}, MOF₂, MOF₃, and MOF_{0.66}.

Claim 40 (Previously Presented): The vapor deposition material of Claim 26, wherein the polycrystalline body, sintered body or single crystal is free of a substrate.